

Diode Sensors Theory

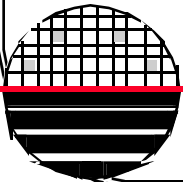
Dr. Lynn Fuller

Dr. Fuller's Webpage: <http://people.rit.edu/lffeee>

Microelectronic Engineering
Rochester Institute of Technology
82 Lomb Memorial Drive
Rochester, NY 14623-5604

Email: Lynn.Fuller@rit.edu

Program Webpage: <http://www.microe.rit.edu>



OUTLINE

Uniform Doped pn Junction

Real pn Junctions

Photodiodes

Light Sources

Diode Temperature Sensors

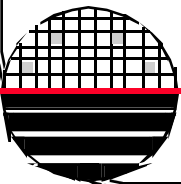
Solar Cells

Applications:

Temperature

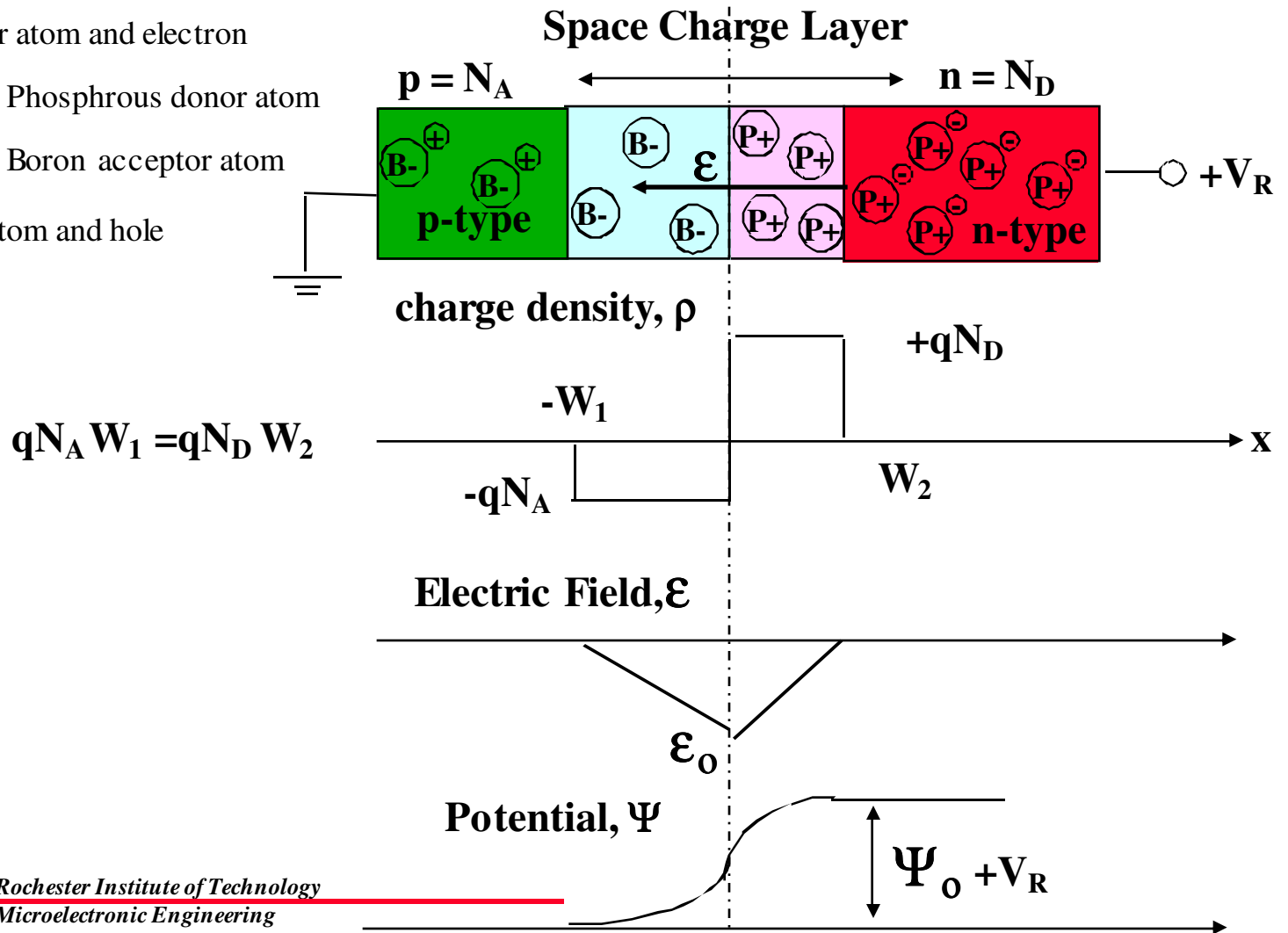
Turbidity

Spectral Radiometer



UNIFORMLY DOPED PN JUNCTION

- $(P^+)^{\ominus}$ Phosphorous donor atom and electron
- (P^+) Ionized Immobile Phosphorous donor atom
- (B^-) Ionized Immobile Boron acceptor atom
- $(B^-)^{\oplus}$ Boron acceptor atom and hole



UNIFORMLY DOPED pn JUNCTION

From Physical Fundamentals:

Potential Barrier - Carrier Concentration: $\Psi_0 = KT/q \ln (N_A N_D / ni^2)$

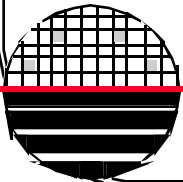
From Electric and Magnetic Fields :

Gauss's Law, Maxwells 1st eqn: $\rho = \nabla \cdot \mathbf{D}$

Relationship between electric flux \mathbf{D} and electric field \mathbf{E} : $\mathbf{D} = \epsilon \mathbf{E}$

Poisson's Equation: $\nabla^2 \Psi_0 = -\rho / \epsilon$

Definition of Electric Field: $\mathbf{E} = -\nabla v$



Ψ_o FROM PHYSICS (FERMI STATISTICS)

$$q(V_{bi}) = (E_i - E_f)_{p\text{-side}} + (E_f - E_i)_{n\text{-side}}$$

$$p = n_i e^{(E_i - E_f)/KT/q}$$

$$n = n_i e^{(E_f - E_i)/KT/q}$$

$$\ln(p/n_i) = \ln e^{(E_i - E_f)/KT/q}$$

$$\ln(n/n_i) = \ln e^{(E_f - E_i)/KT/q}$$

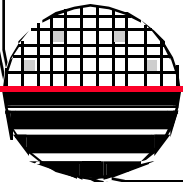
$$KT/q \ln(p/n_i) = (E_i - E_f)_{p\text{-side}}$$

$$KT/q \ln(n/n_i) = (E_f - E_i)_{n\text{-side}}$$

$$\Psi_o = KT/q \ln (N_A N_D / n_i^2)$$

$$n_i = 1.45E10 \text{ cm}^{-3} \text{ for silicon}$$

Where $N_A \approx p$ in p-type silicon and $N_D \approx n$ in n-type silicon



UNIFORMLY DOPED PN JUNCTION

Built in Voltage:

$$\Psi_0 = KT/q \ln (N_A N_D / n_i^2)$$

$$n_i = 1.45E10 \text{ cm}^{-3}$$

Width of Space Charge Layer, W: with reverse bias of V_R volts

$$W = (W_1 + W_2) = [(2\epsilon / q) (\Psi_0 + V_R) (1/N_A + 1/N_D)]^{1/2}$$

W_1 width on p-side

W_2 width on n-side

$$W_1 = W [N_D / (N_A + N_D)]$$

$$W_2 = W [N_A / (N_A + N_D)]$$

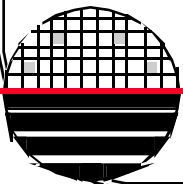
Maximum Electric Field:

$$E_0 = - [(2q/\epsilon) (\Psi_0 + V_R) (N_A N_D / (N_A + N_D))]^{1/2}$$

Junction Capacitance per unit area:

$$C_j' = \epsilon_0 \epsilon_r / W = \epsilon_0 \epsilon_r / [(2\epsilon / q) (\Psi_0 + V_R) (1/N_A + 1/N_D)]^{1/2}$$

$$\begin{aligned} \epsilon &= \epsilon_0 \epsilon_r = 8.85E-12 \text{ (11.7) F/m} \\ &= 8.85E-14 \text{ (11.7) F/cm} \end{aligned}$$



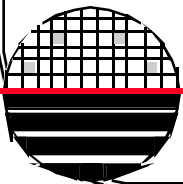
TEMPERATURE DEPENDENCE OF BUILT-IN VOLTAGE

Built in Voltage:

$$\Psi_o = \frac{KT}{q} \ln \left(\frac{N_A N_D}{n_i^2} \right) \quad n_i = 1.45E10 \text{ cm}^{-3} \text{ at } 300 \text{ }^\circ\text{K}$$

$$n_i^2 (T) = A T^3 \exp^{-q E_g / KT} \quad \text{Where } A = 3.977E31$$

$$E_g = E_{g0} - aT^2 / (T+B) \quad \text{Where } a = 0.000702$$
$$B = 1110$$
$$E_{g0} = 1.12 \text{ eV}$$



EXAMPLE CALCULATIONS

Width of space charge layer depends on the doping on both sides and the applied reverse bias voltage and temperature.

ROCHESTER INSTITUTE OF TECHNOLOGY
 MICROELECTRONIC ENGINEERING

PN.XLS
 4/16/2011

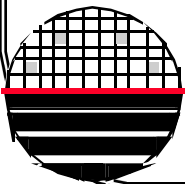
DR. LYNN FULLER

To use this spreadsheet change the values in the white boxes. The rest of the sheet is protected and should not be changed unless you are sure of the consequences. The calculated results are shown in the purple boxes.

CONSTANTS		VARIABLES	
K	1.38E-23 J/K	Temp	<input type="text" value="300"/> K
q	1.60E-19 Coul		
Ego	1.12 eV		
zo	8.85E-14 F/cm	Nd =	<input type="text" value="1.00E+16"/> cm-3
zf	11.7	Na =	<input type="text" value="5.00E+14"/> cm-3
ni	1.45E+10 cm-3		
Breakdown E	3.00E+05 V/cm	Vr =	<input type="text" value="0"/> Volts Reverse Bias Voltage

CALCULATIONS:

$E_g = E_{go} - (aT^2)/(T+B)$	1.075	eV
$n_i^2 = A T^3 e^{(-E_g/KT/q)}$	9.84E+20	cm-6
$KT/q =$	0.0259	Volts
$V_{bi} = (KT/q) \ln (N_a N_d / n_i^2)$	0.58	Volts
$W = [(2\epsilon/q)(V_{bi} + V_r)(1/N_a + 1/N_d)]^{0.5}$	1.25	μm
$W_1 = W[N_d/(N_a + N_d)]$	1.19	μm
$W_2 = W[N_a/(N_a + N_d)]$	0.06	μm
$E_o = -[(2q/\epsilon_o \epsilon_r)(V_{bi} + V_a)(N_a N_d / (N_a + N_d))]^{0.5}$	-9.23E+03	V/cm
$C_j' = \epsilon_o \epsilon_r / W$	8.26E-09	F/cm ²



EXAMPLE

Example: If the doping concentrations are $N_A=1E15$ and $N_D=3E15$ cm^{-3} and the reverse bias voltage is 0, then find the built in voltage, width of the space charge layer, width on the n-side, width on the p-side, electric field maximum and junction capacitance. Repeat for reverse bias of 10, 40, and 100 volts.

$$\Psi_0 = V_{bi} = \frac{KT}{q} \ln \left(\frac{N_A N_D}{n_i^2} \right) =$$

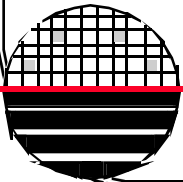
$$W = (W_1 + W_2) = \left[\frac{2\epsilon}{q} (\Psi_0 + V_R) \left(\frac{1}{N_A} + \frac{1}{N_D} \right) \right]^{1/2} =$$

$$W_1 =$$

$$W_2 =$$

$$E_{max} =$$

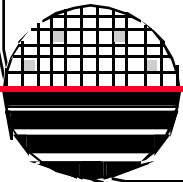
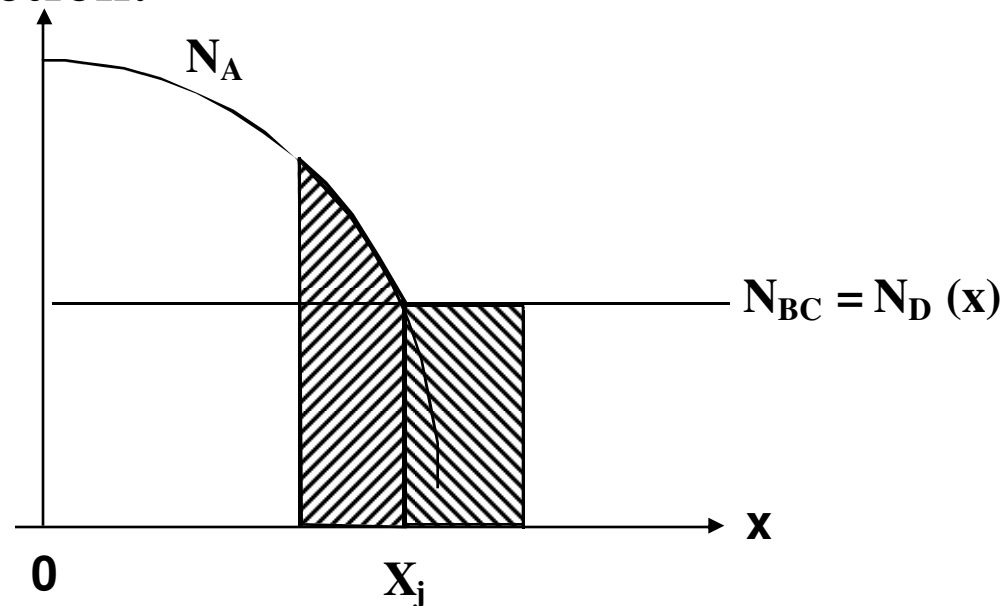
$$C_j =$$



REAL JUNCTION

Real pn junctions: The uniformly doped abrupt junction is rarely obtained in integrated circuit devices. (epi layer growth is close).

Diffused pn junction:

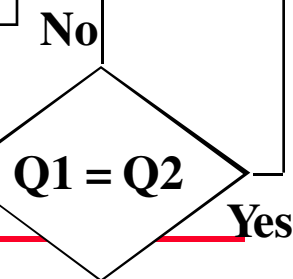


REAL *pn* JUNCTION

Given, X_j , $N_A(X)$, $N_D(X)$

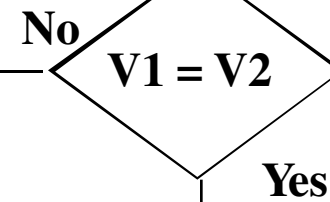
Pick an X_1 to the left of X_j .
Calculate the total charge per unit area in the region between X_1 and X_j . This charge is Q_1 .

Pick an X_2 to the right of X_j .
Calculate the total charge per unit area in the region between X_2 and X_j . This charge is Q_2 .

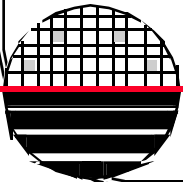


Calculate potential V_1 from physical fundamentals:
 $V_1 = \frac{KT}{q} \ln \left(\frac{N_A N_D}{n_i^2} \right) + V_R$

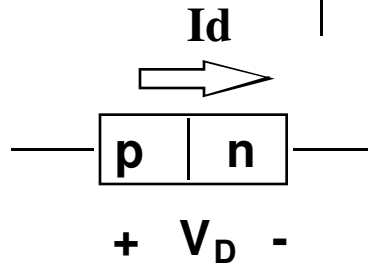
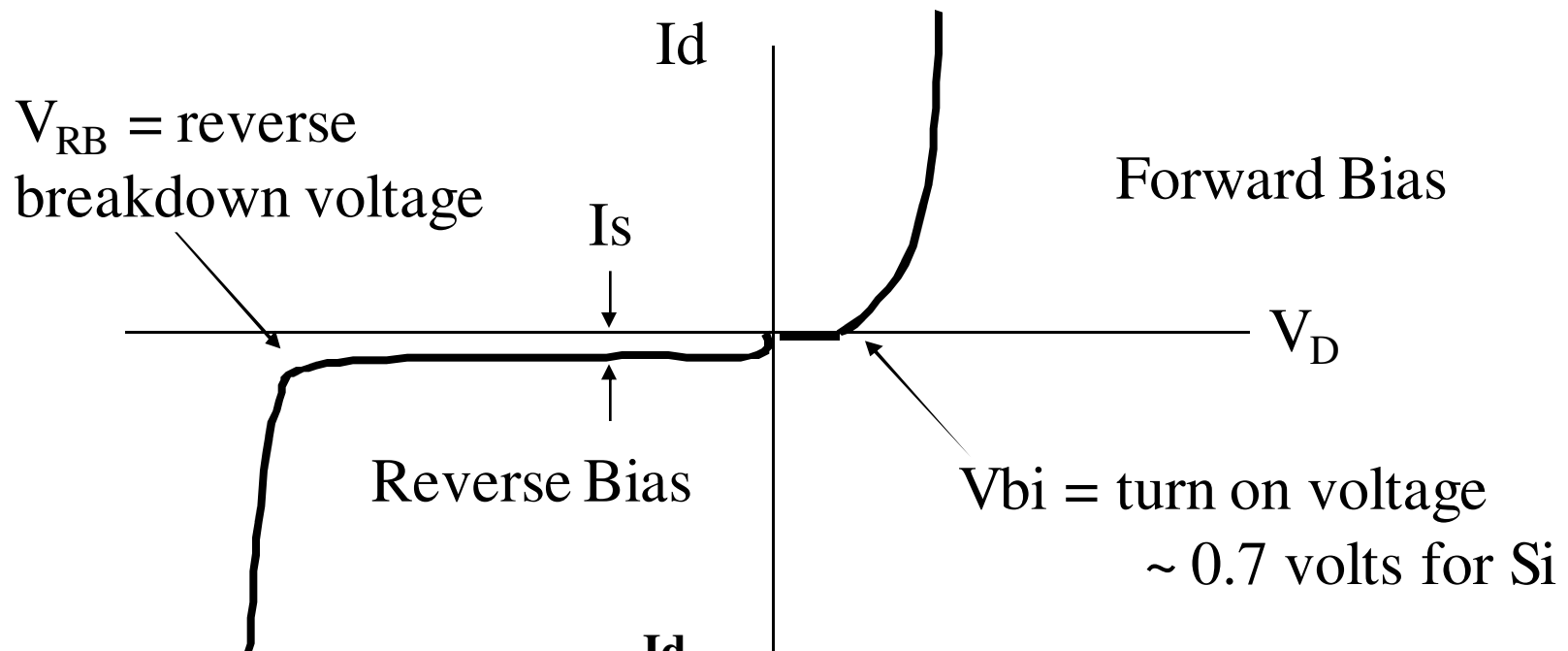
Calculate potential V_2 from E & M fields fundamentals:
 $\nabla^2 \Psi_0 = -\rho / \epsilon$



Calculate $W_1 = X_1$, $W_2 = X_2$
 $L = W_1 + W_2$, C_j , other

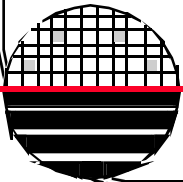


CURRENTS IN PN JUNCTIONS

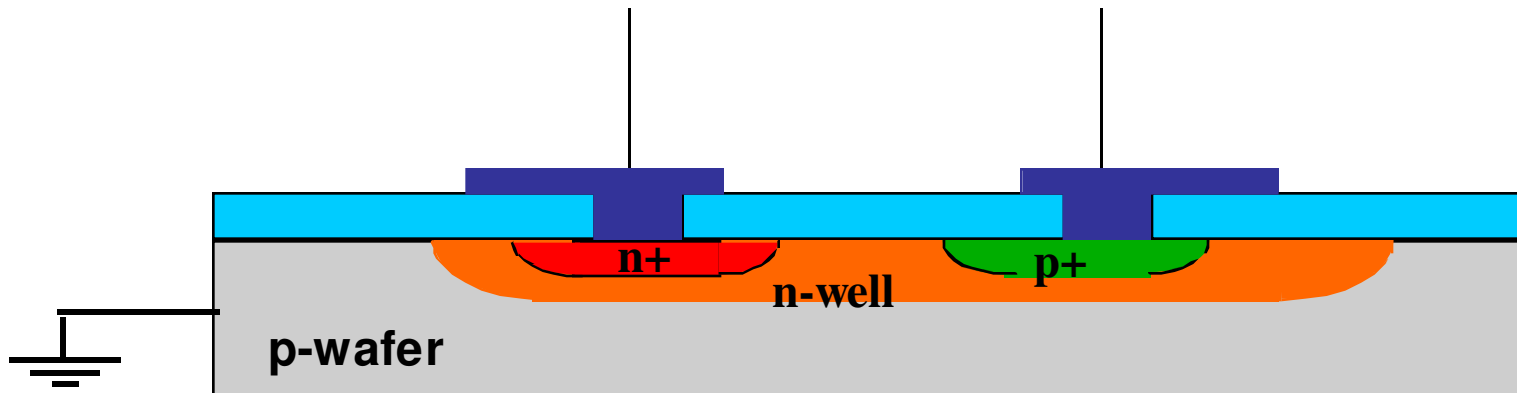


$$I_d = I_s [EXP (q V_D / K T) - 1]$$

Ideal diode equation

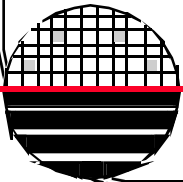


INTEGRATED DIODES



p+ means heavily doped p-type
n+ means heavily doped n-type
n-well is an n-region at slightly higher doping than the p-wafer

Note: there are actually two pn junctions, the well-wafer pn junction should always be reverse biased



Diode Sensors Theory

REAL DIODES

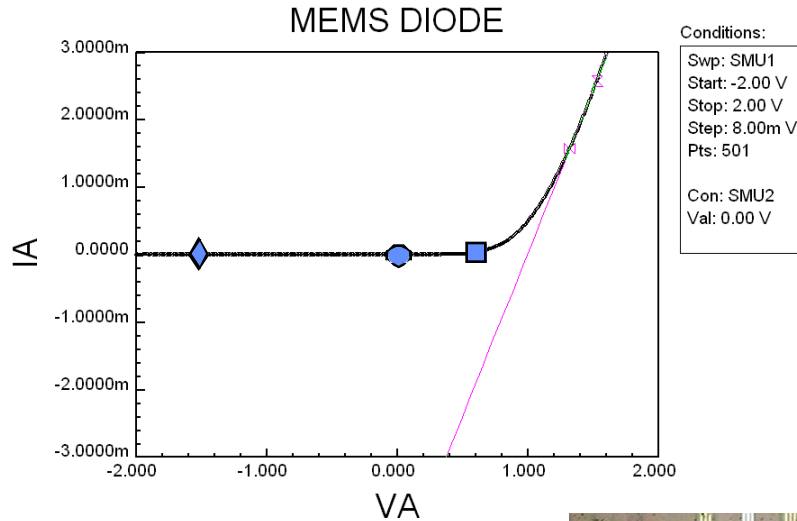
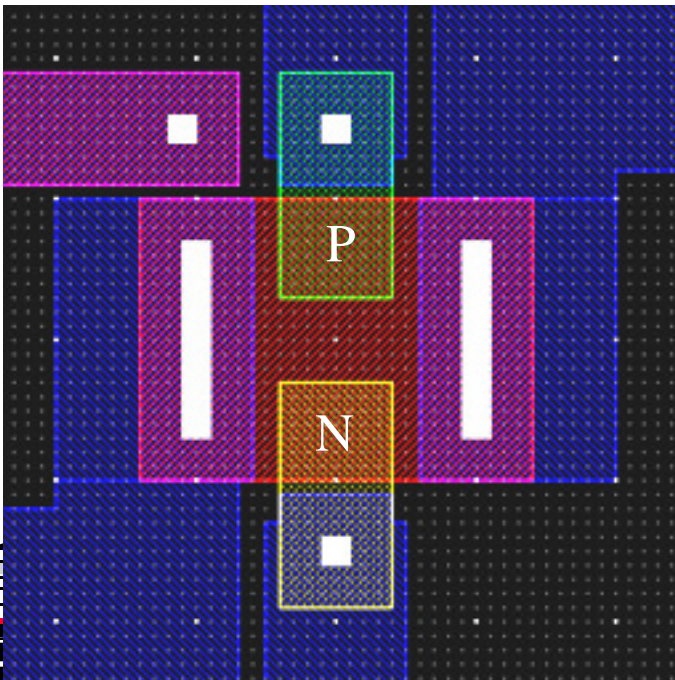
Series Resistance = $1/4.82\text{m} = 207$

Junction Capacitance ~ 2 pF

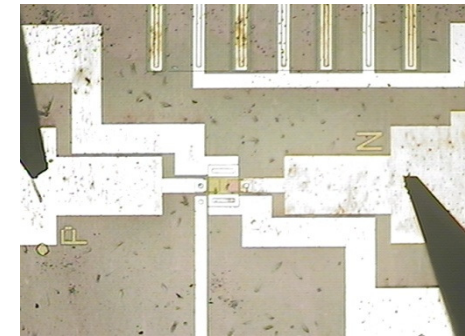
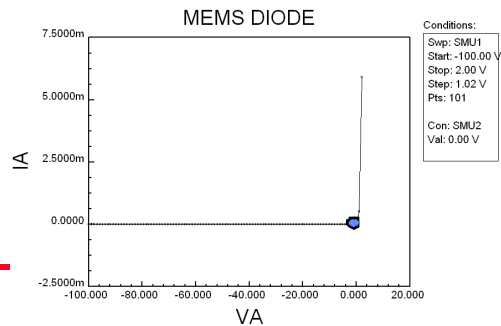
$I_s = 3.02\text{E-}9$ amps

$BV = > 100$ volts

Size $80\mu \times 160\mu$



Fit #1:	Fit #2:	Cursors: X	Y
Type: Cursor	None	□ 0.60	0.03m
Slp:4.82m	****	◇ -1.52	-3.02n
Yint:-4.79m	****	○ 0.00	0.38n
Xint:0.99	***	⊗ 1.53	2.57m
ICS	10:11:40	⊗ 1.32	1.57m
	03/05/2009	△	



DIODE SPICE MODEL

Model Parameter	Default Value	MEMS Diode Extracted Value
Is reverse saturation current	1e-14 A	3.02E-9 A
N emission coefficient	1	1
RS series resistance	0	207 ohms
VJ built-in voltage	1 V	0.6
CJ0 zero bias junction capacitance	0	2pF
M grading coefficient	0.5	0.5
BV Breakdown voltage	infinite	400
IBV Reverse current at breakdown	1E-10 A	-

```
DXXX N(anode) N(cathode) Modelname  
.model Modelname D Is=1e-14 Cjo=.1pF Rs=.1  
.model RITMEMS D IS=3.02E-9 N=1 RS=207  
+VJ=0.6 CJ0=2e-12 M=0.5 BV=400
```

DIODE TEMPERATURE DEPENDENCE

$$I_d = I_s [\text{EXP} (q V_D/KT) - 1]$$

Neglect the -1 in forward bias, Solve for V_D

$$V_D = (KT/q) \ln (I_d/I_s) = (KT/q) (\ln(I_d) - \ln(I_s)) \quad \text{eq 1}$$

Take dV_D/dT : note I_d is not a function of T but I_s is

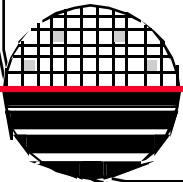
$$dV_D/dT = (KT/q) (\underbrace{d\ln(I_d)/dT}_{\text{zero}} - d\ln(I_s)/dT) + K/q (\underbrace{\ln(I_d) - \ln(I_s)}_{V_D/T \text{ from eq 1}})$$

Rewritten

$$dV_D/dT = V_D/T - (KT/q) ((1/I_s) dI_s/dT) \quad \text{eq 2}$$

Now evaluate the second term, recall

$$I_s = qA (D_p/(L_p N_d) + D_n/(L_n N_a)) n_i^2$$



DIODE TEMPERATURE DEPENDENCE

and $n_i^2(T) = A T^3 e^{-qE_g/KT}$

This gives the temperature dependence of I_s

$$I_s = C T^2 e^{-qE_g/KT} \quad \text{eq 3}$$

Now take the natural log

$$\ln I_s = \ln (C T^2 e^{-qE_g/KT})$$

Take derivative with respect to T

$$(1/I_s) d(I_s)/dT = d[\ln(C T^2 e^{-qE_g/KT})]/dT = (1/I_s) d(CT^2 e^{-qE_g/KT})/dT$$

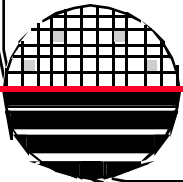
$$= (1/I_s) [CT^2 e^{-qE_g/KT}(qE_g/KT^2) + (Ce^{-qE_g/KT})2T]$$

$$= (1/I_s) [I_s(qE_g/KT^2) + (2I_s/T)]$$

Back to eq 2

$$dV_D/dT = V_D/T - (KT/q) [(qE_g/KT^2) + (2/T)]$$

$$dV_D/dT = V_D/T - E_g/T - 2K/q$$

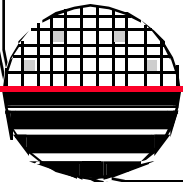
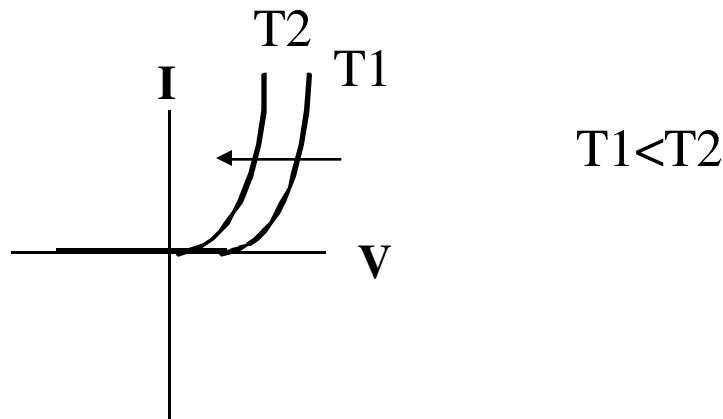


EXAMPLE: DIODE TEMPERATURE DEPENDENCE

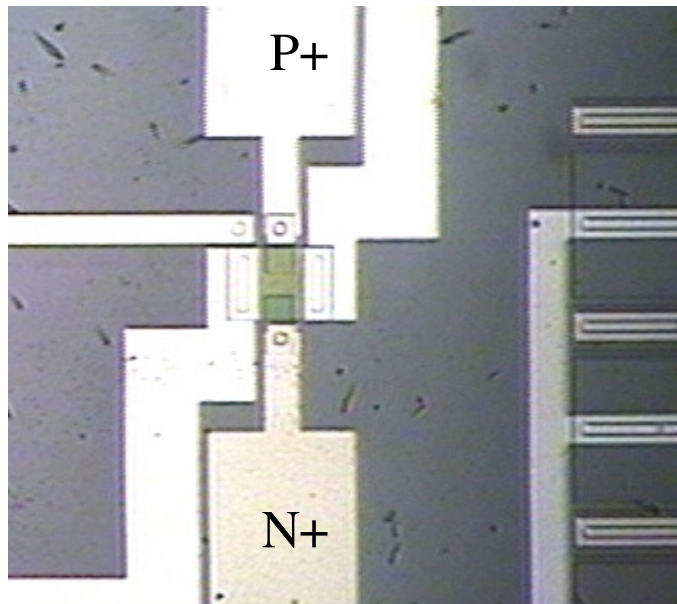
$$dV_D/dT = V_D/T - E_g/T - 2K/q$$

Silicon with $E_g \sim 1.2 \text{ eV}$, $V_D = 0.6 \text{ volts}$, $T=300 \text{ }^\circ\text{K}$

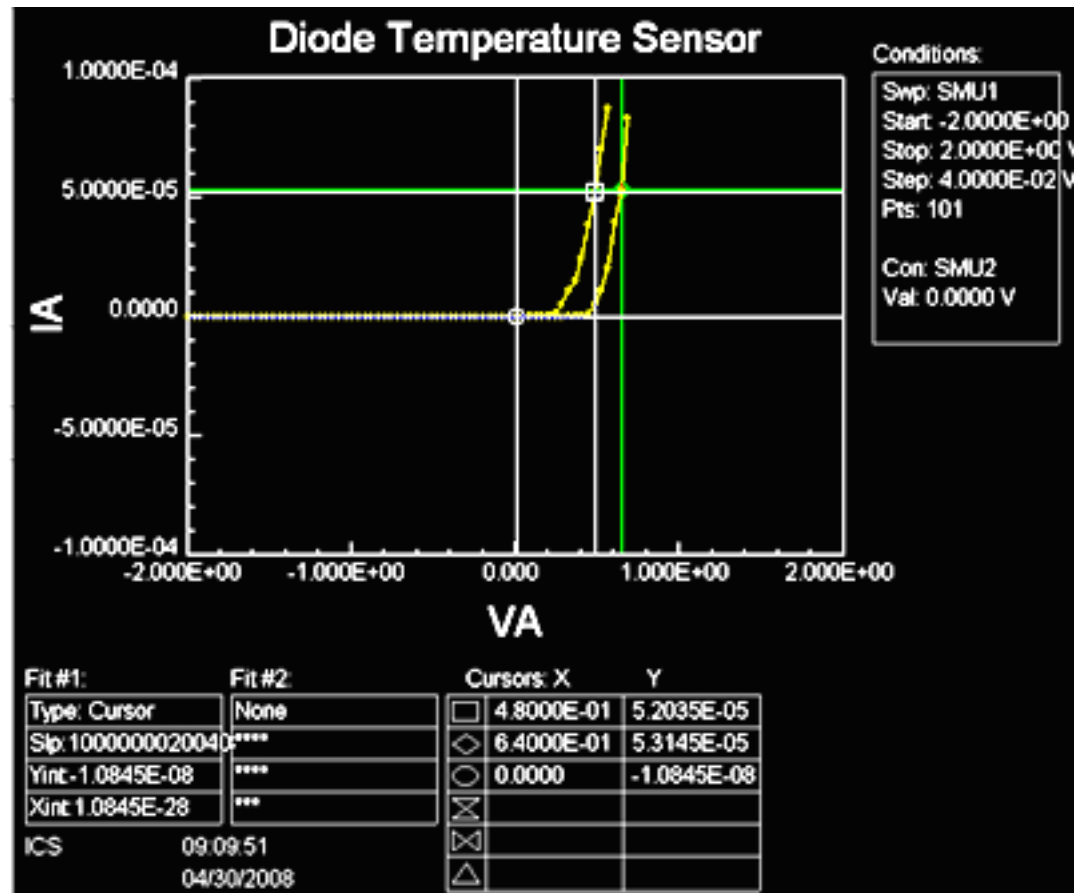
$$\begin{aligned} dV_D/dT &= .6/300 - 1.2/300 - (2(1.38\text{E-}23)/1.6\text{E-}19) \\ &= -2.2 \text{ mV/}^\circ \end{aligned}$$



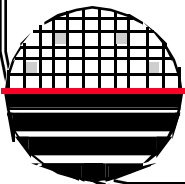
DIODE AS A TEMPERATURE SENSOR



Poly Heater
Buried pn Diode,
N+ Poly to Aluminum
Thermocouple

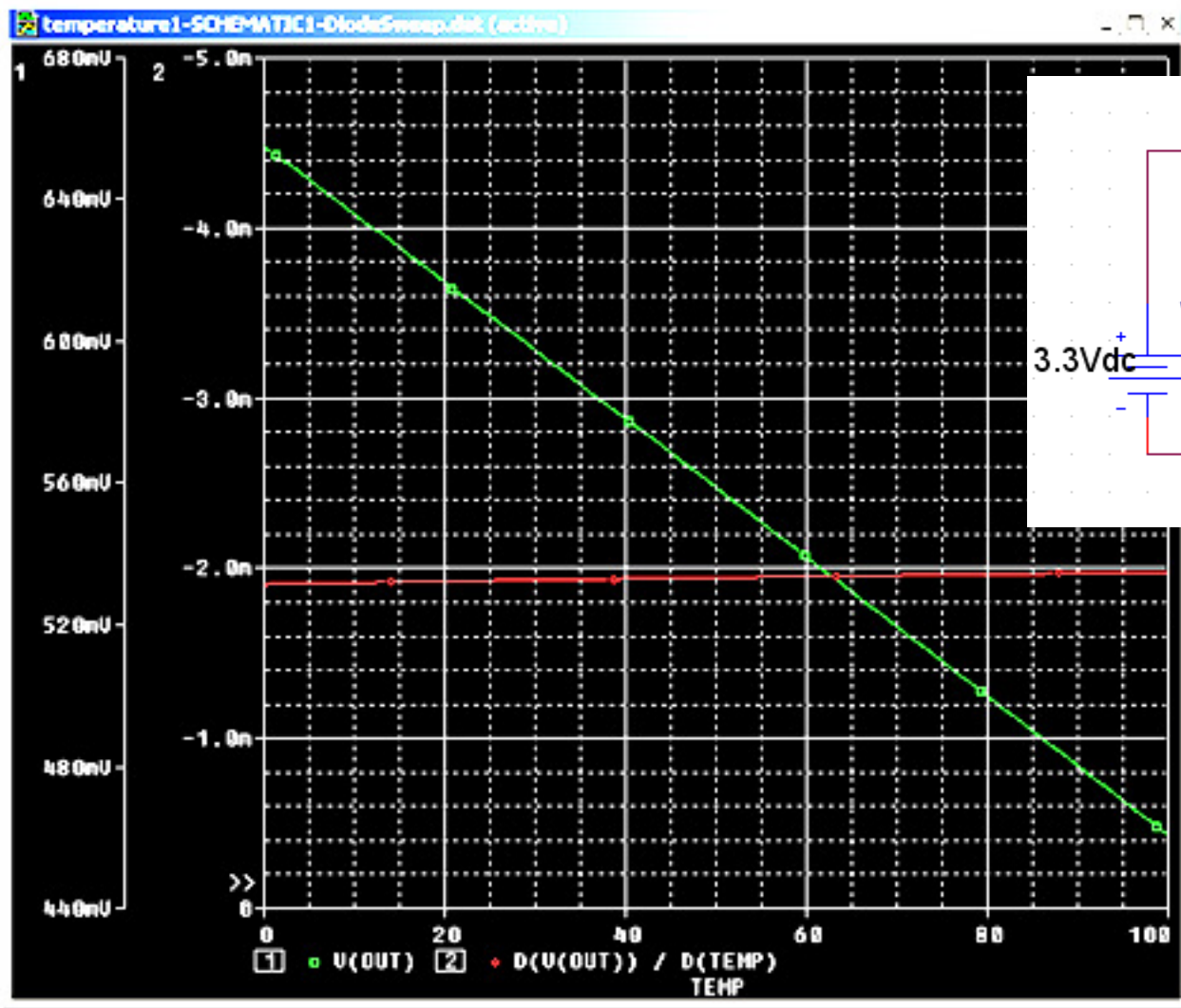


Compare with theoretical $-2.2\text{mV}/^\circ\text{C}$



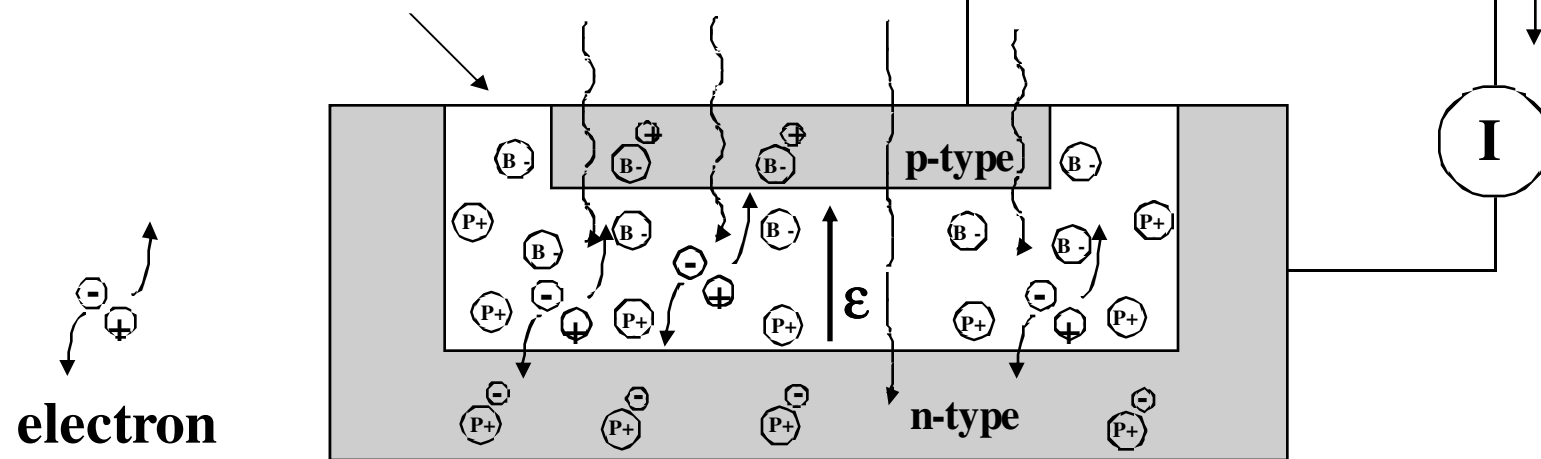
Diode Sensors Theory

SPICE FOR DIODE TEMPERATURE SENSOR



PHOTODIODE

space charge layer



electron and hole pair



Phosphorous donor atom and electron



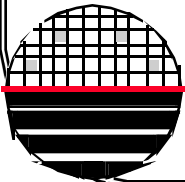
Ionized Immobile Phosphorous donor atom



Ionized Immobile Boron acceptor atom



Boron acceptor atom and hole



CHARGE GENERATION vs WAVELENGTH

$$E = h\nu = hc / \lambda$$

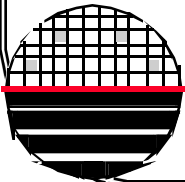
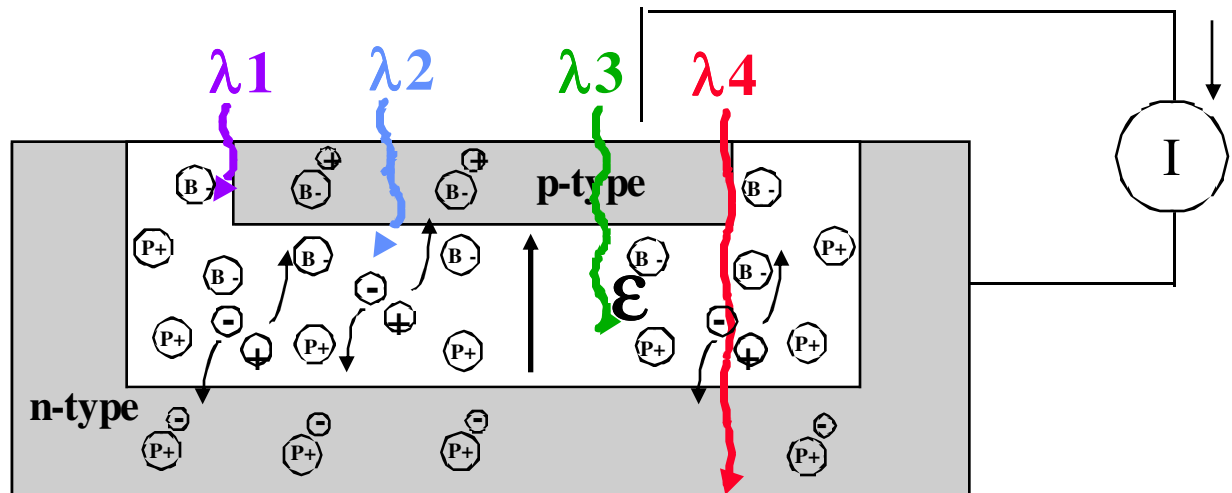
$$h = 6.625 \text{ e-34 j/s}$$

$$= (6.625 \text{ e-34}/1.6\text{e-19}) \text{ eV/s}$$

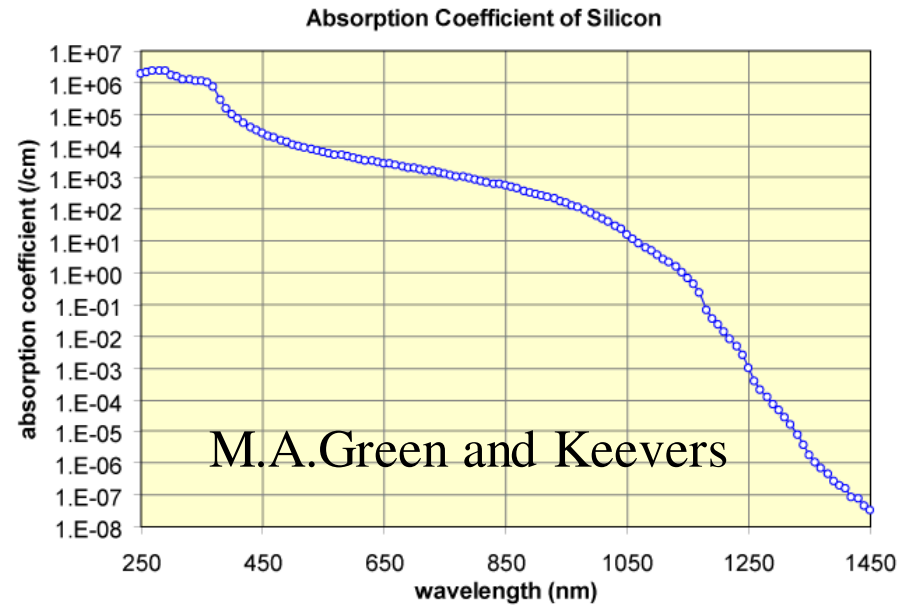
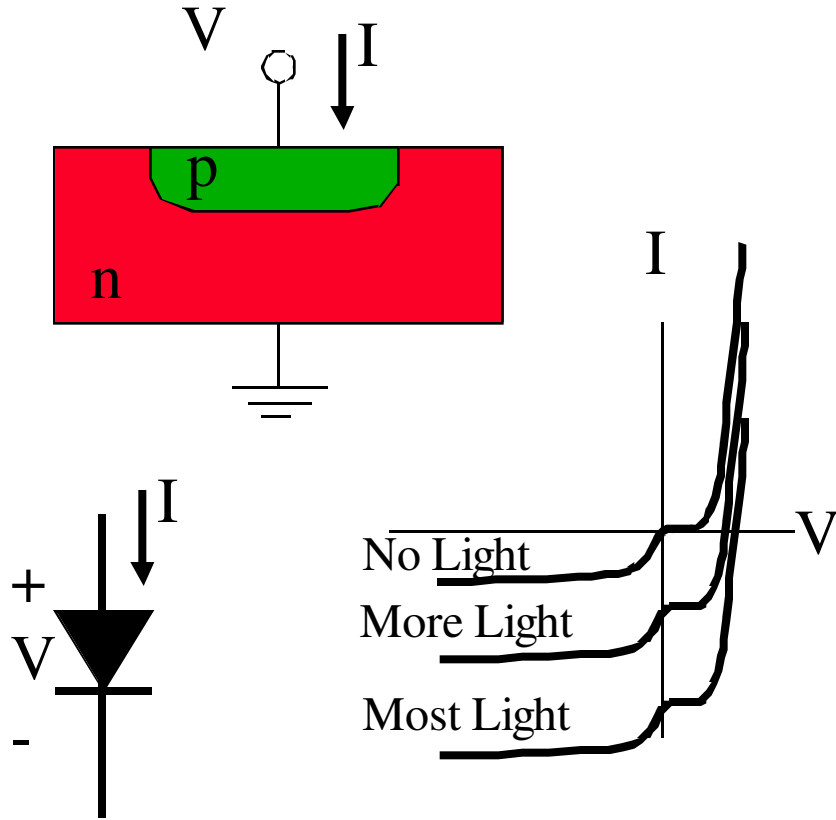
$$E = 1.55 \text{ eV (red)}$$

$$E = 2.50 \text{ eV (green)}$$

$$E = 4.14 \text{ eV (blue)}$$

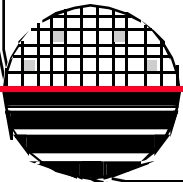


ADSORPTION VERSUS DISTANCE

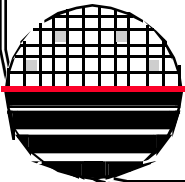
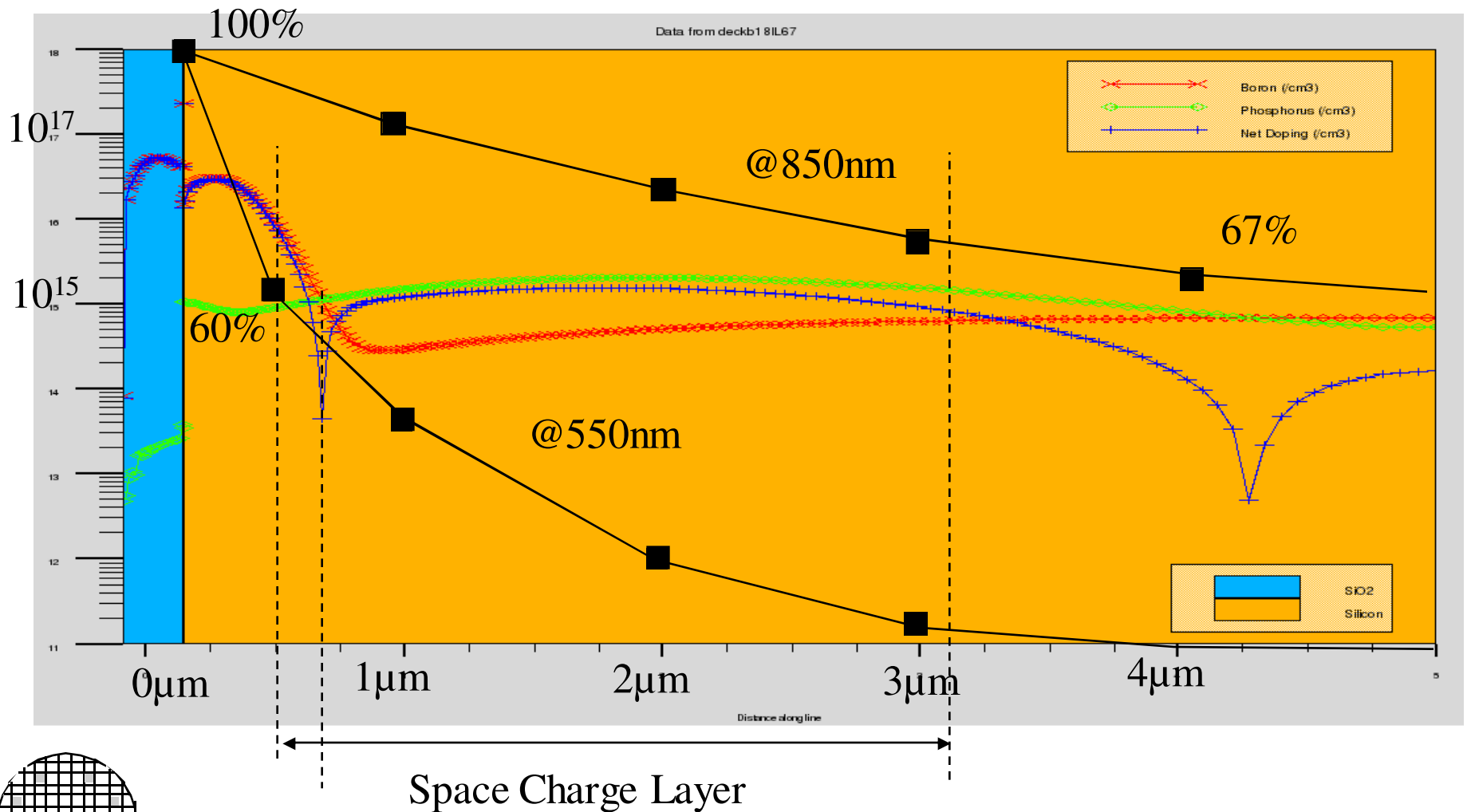


$$\phi(x) = \phi(0) \exp^{-\alpha x}$$

Find % adsorbed for Green light at $x=5 \mu\text{m}$ and Red light at $5 \mu\text{m}$



PN JUNCTION DESIGN FOR PHOTO DIODE



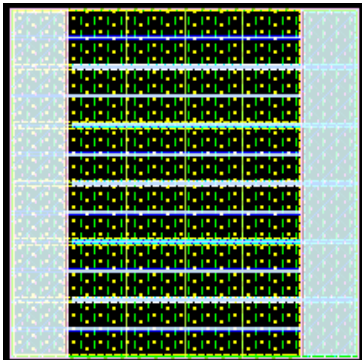
MICROELECTRONIC ENGINEERING

Diode Sensors Theory

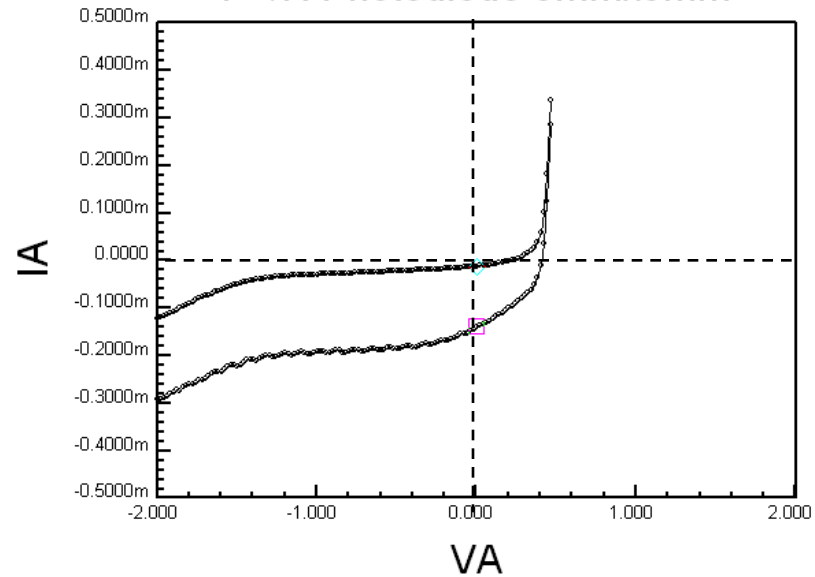
LARGE 5mm X 5mm PHOTODIODE



5mm
X
3.33mm



P+/N Photodiode 5mmx5mm

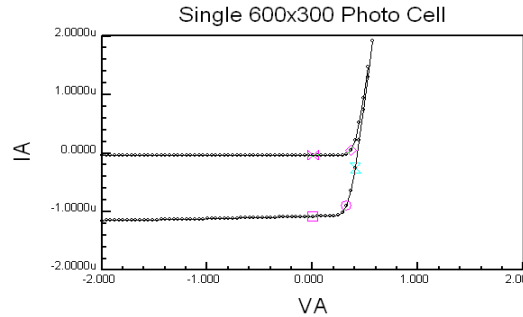
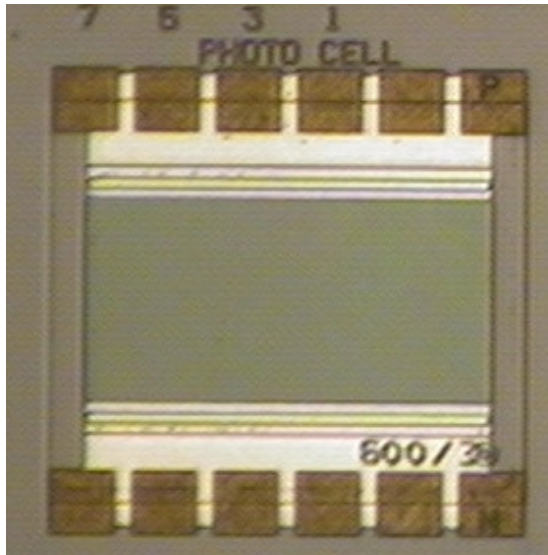


Fit #1:	Fit #2:	Cursors: X Y		
None	None	□	0.00000	-0.14080m
****	****	◇	0.00000	-0.01383m
****	****	○		
***	***	⊗		
		⊗		
		△		

ICS 13:46:58 11/18/2009

$I_{sc} = 0.15\text{mA}$ (short circuit current)
or 9.09 A/m^2

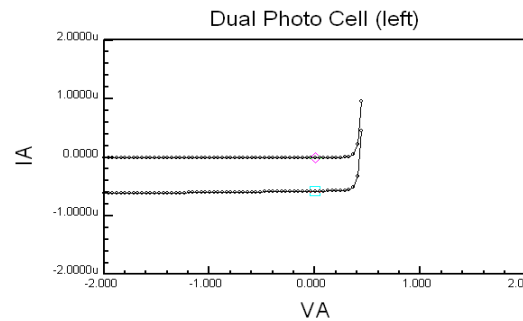
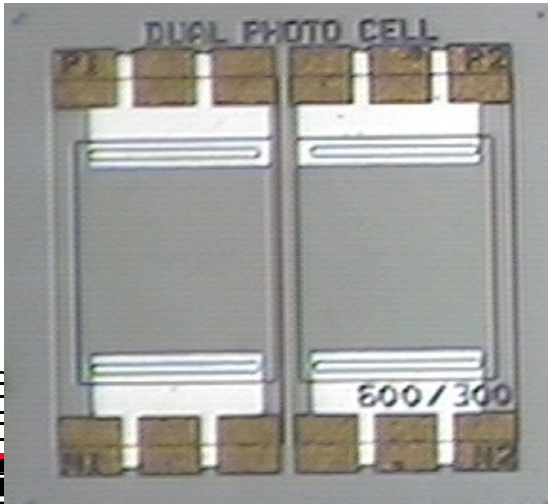
SINGLE AND DUAL PHOTO CELL



Conditions:
 Swp: SMU1
 Start: -2.00000 V
 Stop: 2.00000 V
 Step: 0.04000 V
 Pts: 101
 Con: SMU2
 Val: 0.00000 V

$I_{sc} = 1.088 \text{ uA}$
 or 6 A/m^2

Fit #1:	Fit #2:	Cursors: X	Y
None	None	0.00000	-1.08800u
****	****	0.36000	0.04135u
****	****	0.32000	-0.90894u
***	***	0.40000	-0.26045u
ICS	10:48:12 10/27/2009	0.00000	-0.04408u



Conditions:
 Swp: SMU1
 Start: -2.00000 V
 Stop: 2.00000 V
 Step: 0.04000 V
 Pts: 101
 Con: SMU2
 Val: 0.00000 V

$I_{sc} = 0.585 \text{ uA}$
 or 3.25 A/m^2

Fit #1:	Fit #2:	Cursors: X	Y
None	None	0.00000	-0.58580u
****	****	0.00000	-7.96390n
****	****		
***	***		
ICS	11:29:09 10/27/2009		

SOLAR CELL TUTORIAL

SOME TERMS AND DEFINITIONS:

Air Mass – amount of air between sun and solar cell. In space $AM=0$ at the equator at noon $AM=1$, if the sun is arriving at an angle θ , $AM=1/\cos \theta$. $AM1.5$ is the standard for most solar cell work in USA and gives a sum total of $1000\text{w}/\text{m}^2$ over the entire spectrum of wavelengths from $0.2\mu\text{m}$ to $2.0\mu\text{m}$

Efficiency is the ratio of the power out of a solar cell to the power falling on the solar cell (normally $1000\text{w}/\text{m}^2$ with the $AM1.5$ spectrum) Since Si solar cells can not absorb much of the infrared spectrum from the sun, and other factors, typical efficiencies are limited to 26-29% for basic silicon solar cells.

Quantum Efficiency – normalized ratio of electrons and holes collected to photons incident on the cell at a single wavelength, given in %.

FF – Fill Factor, a figure of merit, the “squareness “ of the diode I-V characteristic in 4th quadrant with light falling on the cell.

SOLAR CELL TUTORIAL

From: Solar Cells, Martin A. Green, Prentice Hall

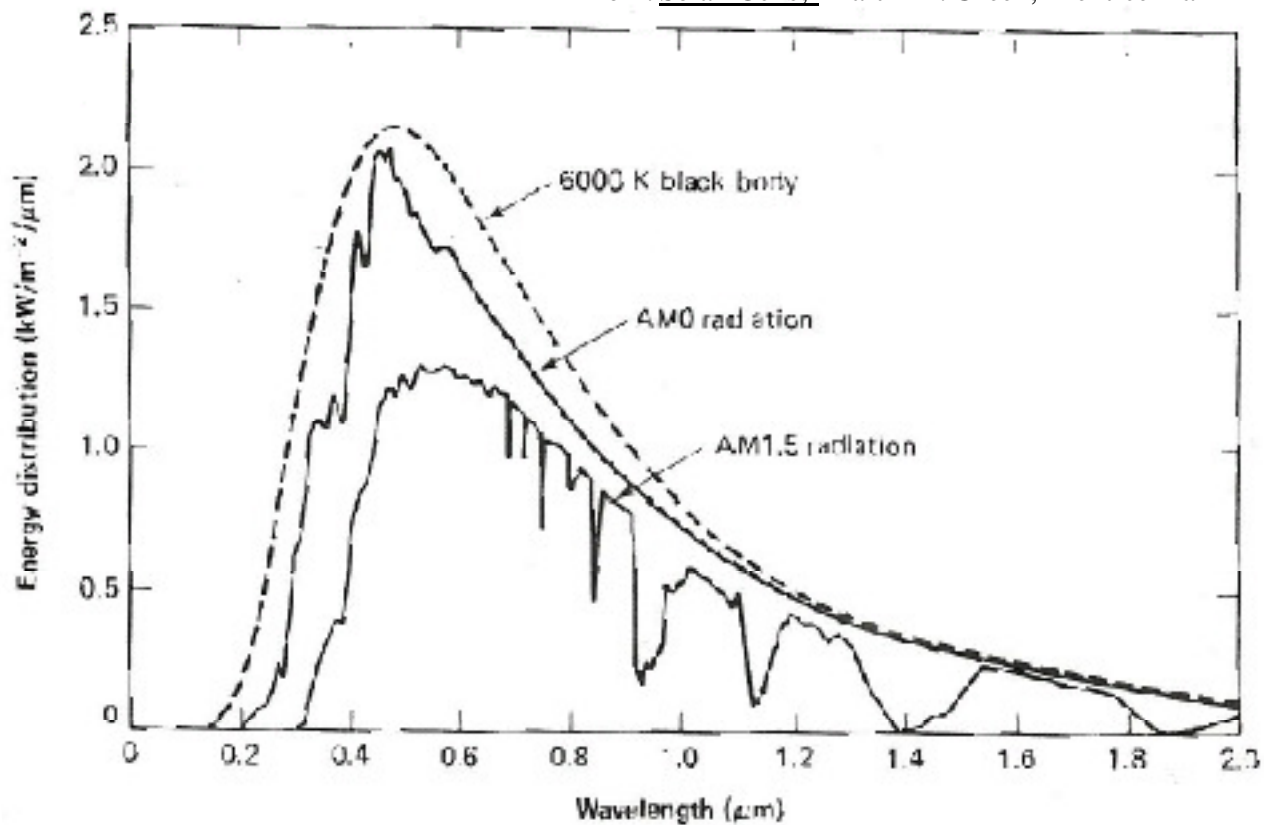
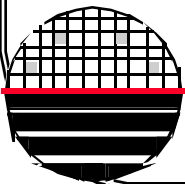
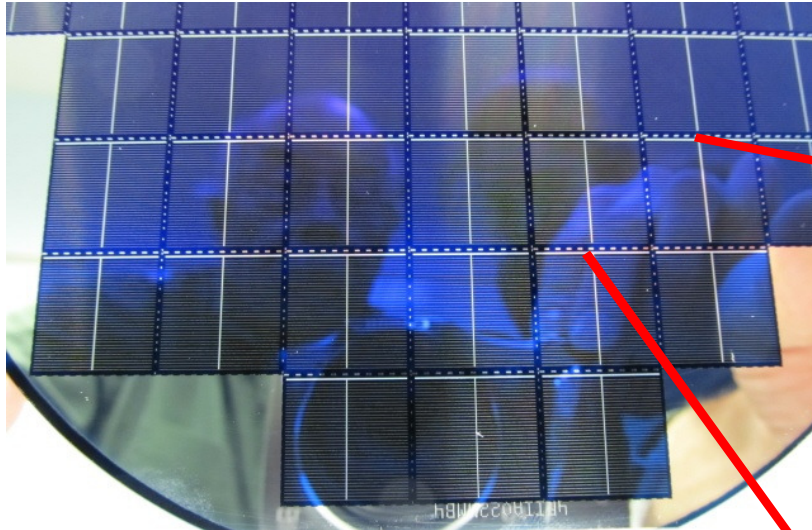


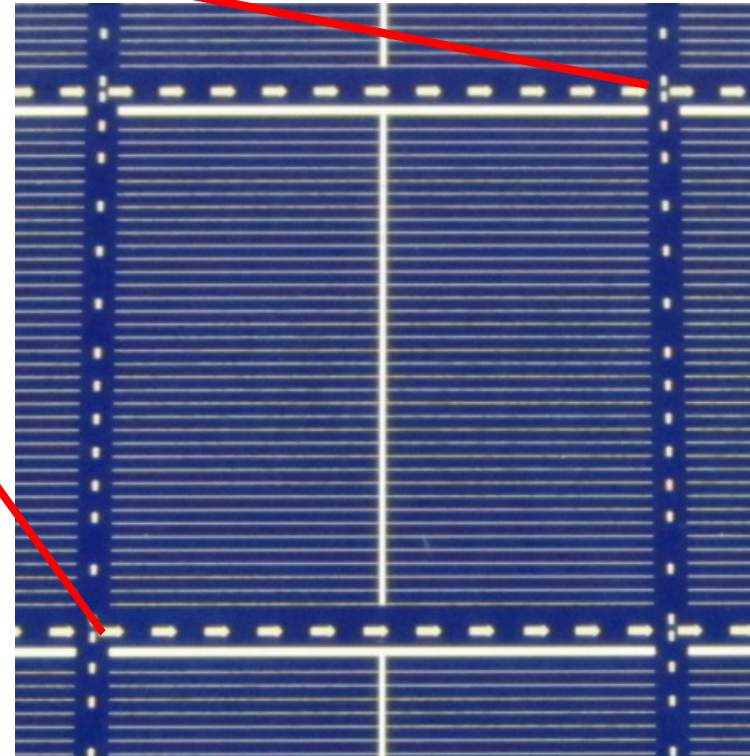
Figure 1.3. Spectral distribution of sunlight. Shown are the cases of AM0 and AM1.5 radiation together with the radiation distribution expected from the sun if it were a black body at 6000K.



PHOTOCELL-ELLEN SEDLACK SENIOR PROJECT

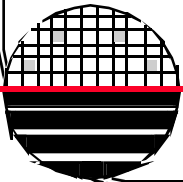


16000um x 16000um

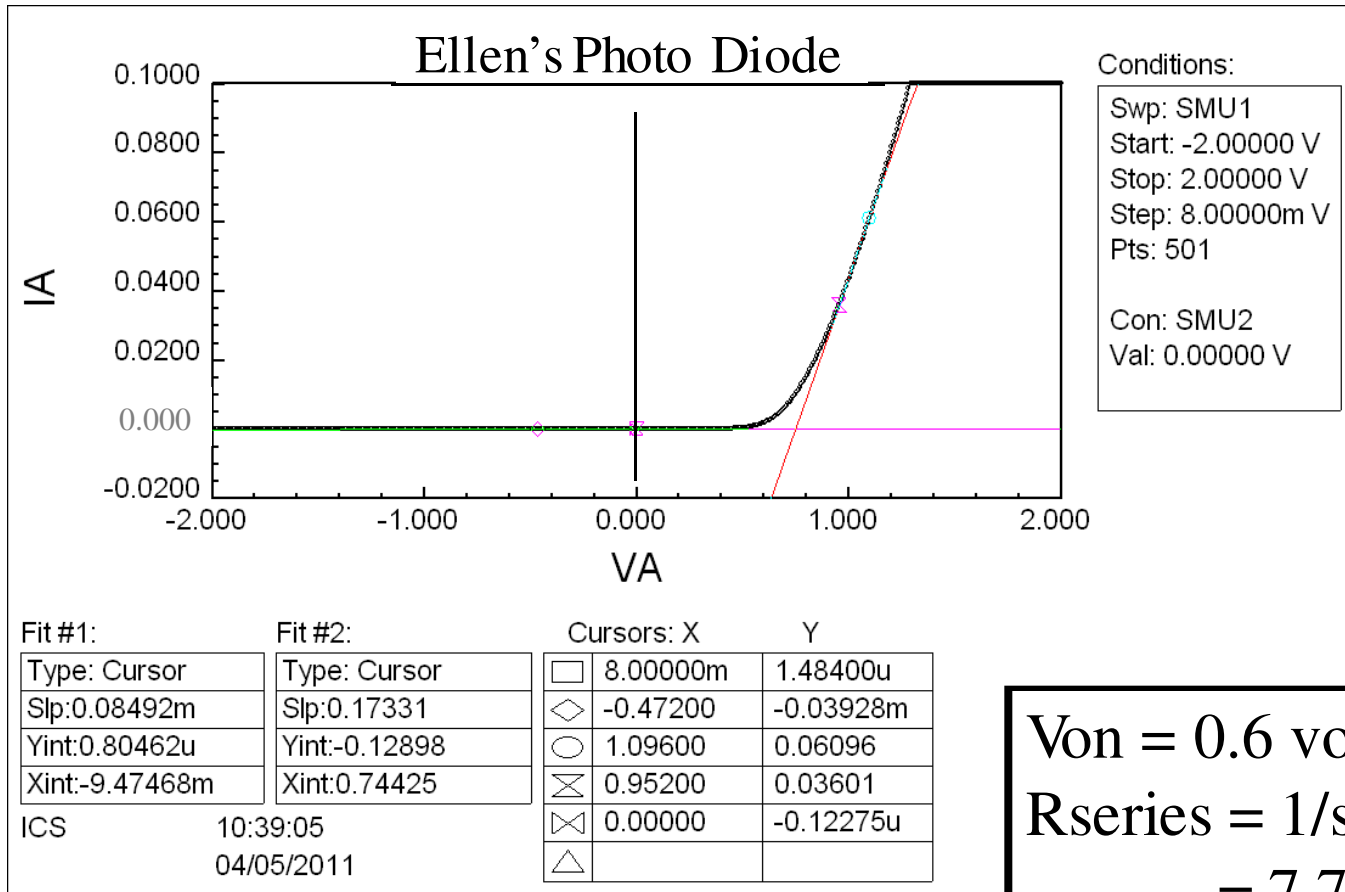


Ellen Sedlack 2011

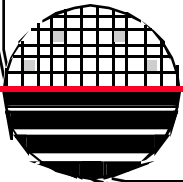
*Rochester Institute of Technology
Microelectronic Engineering*



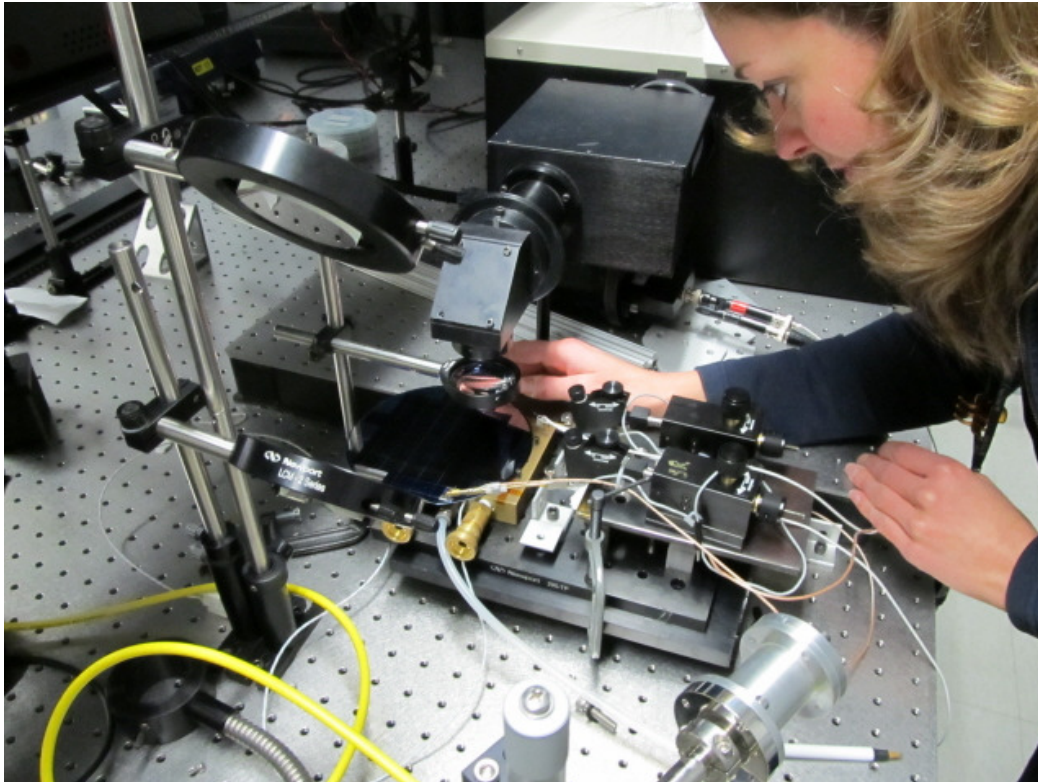
I-V CHARACTERISTICS OF PHOTO CELL



$V_{on} = 0.6 \text{ volts}$
 $R_{series} = 1/\text{slope} = 1/0.129$
 $= 7.75 \text{ ohms}$
 $I_s = 1.48 \mu\text{A (in room light)}$

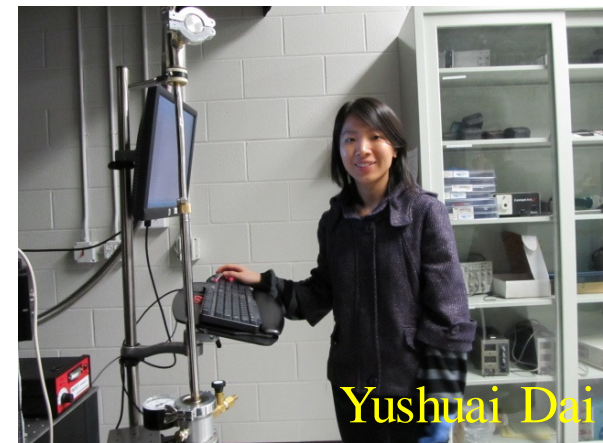
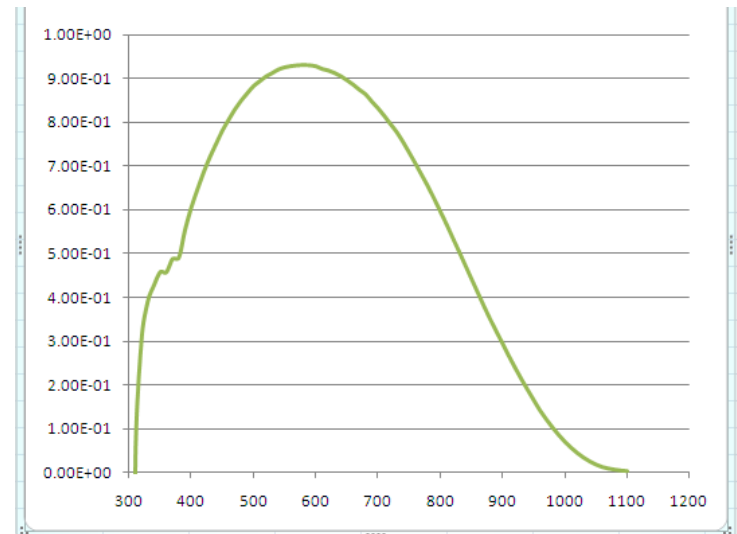


PHOTOCELL - QUANTUM EFFICIENCY

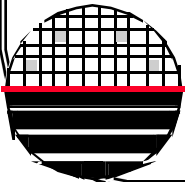


Ellen Sedlack 2011

93% between 550nm and 650nm

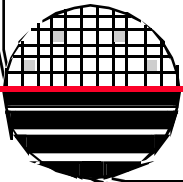
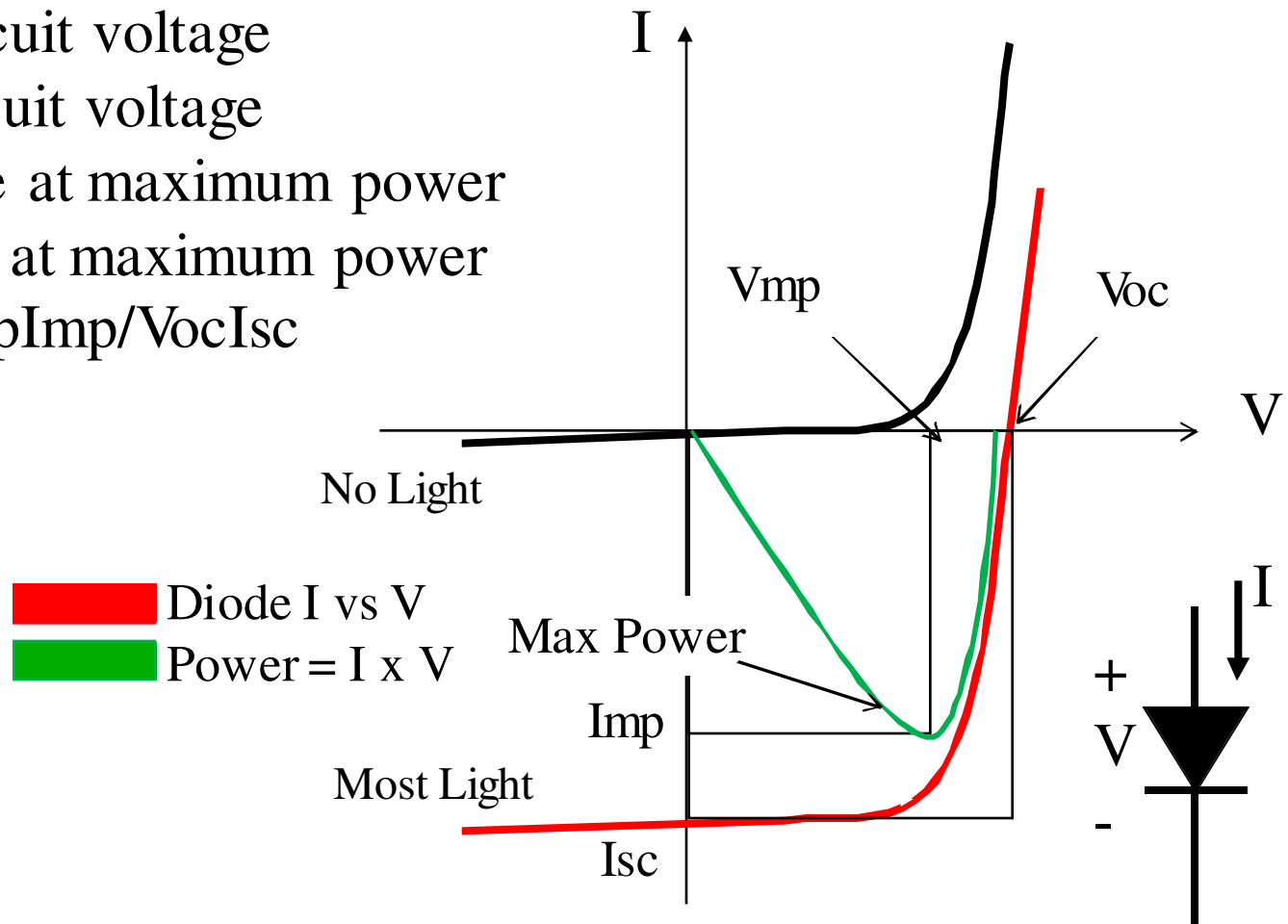


Yushuai Dai



SOLAR CELL TUTORIAL

- Voc** - open circuit voltage
- Isc** – short circuit current
- Vmp** – Voltage at maximum power
- Imp** – Current at maximum power
- FF** – $FF = V_{mp}I_{mp}/V_{oc}I_{sc}$

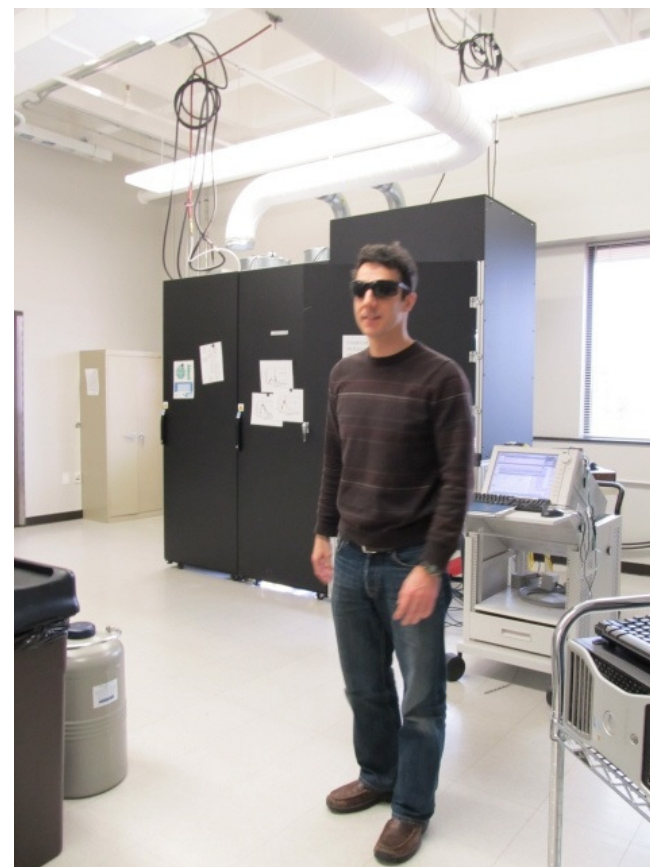
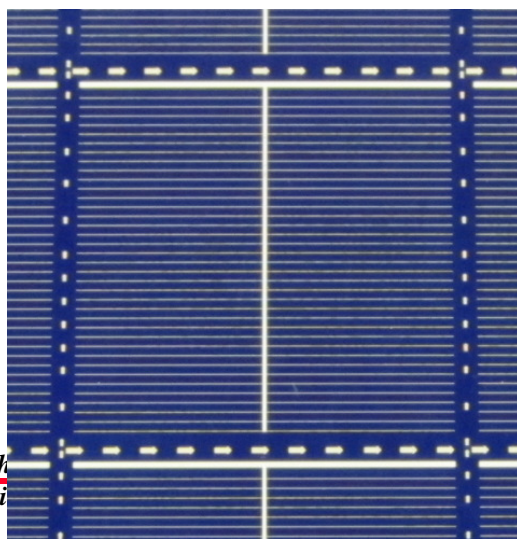


PHOTOCELL – POWER EFFICIENCY

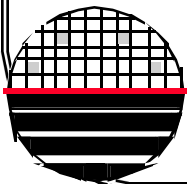
AM 1.5 Light Source



Zachary Bittner



Ivan Puchades

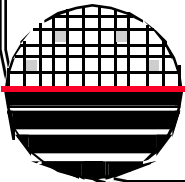
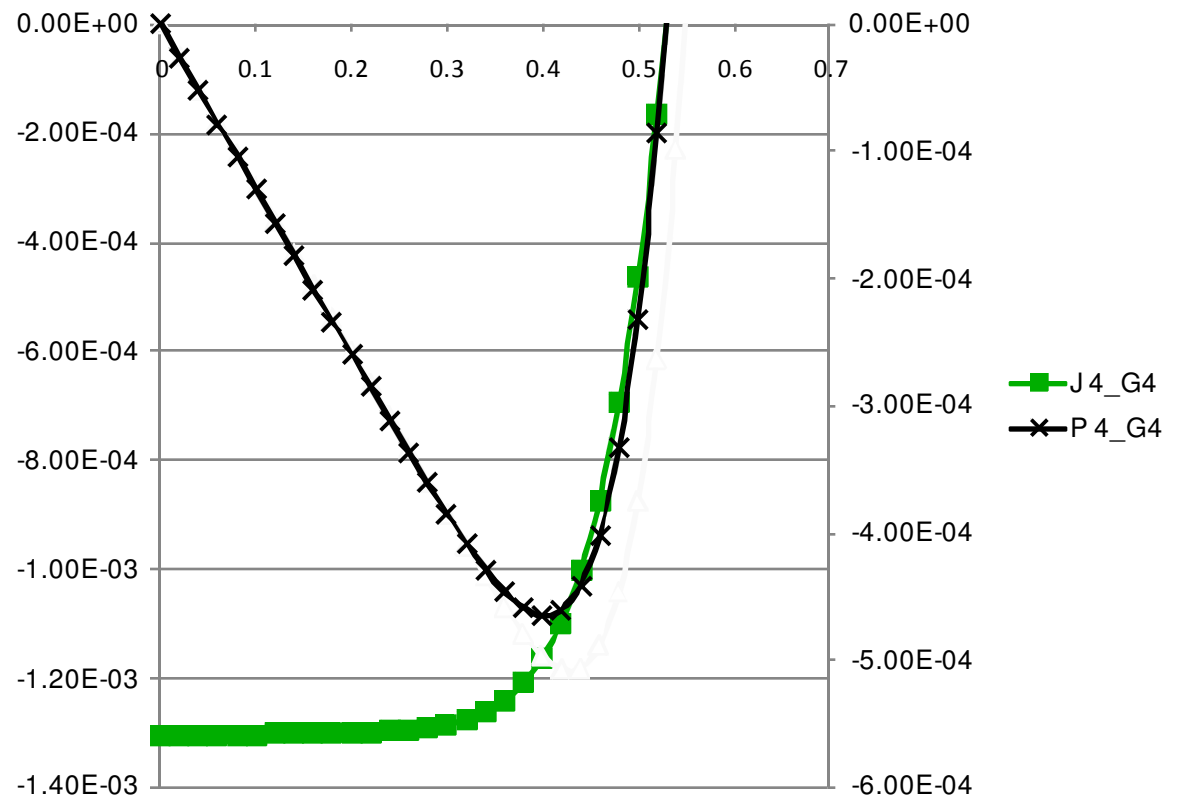


Diode Sensors Theory

POWER, EFFICIENCY, I_{sc} , V_{oc}

Setting	Spot size (mm)	Cell size (cm)	Current (A)	J (A/cm ²)	Irradiance (mW/cm ²)
2.25x @max	1.267	0.25	2.77E-04	1.11E-03	3.39

Column1	P 4_G5	P 4_G4
Pmax	-5.06E-04	-4.65E-04
Jmax	-1.21E-03	-1.160E-03
Vmax	0.42	0.380
Jsc	-1.30E-03	-1.30E-03
Voc	5.60E-01	0.540
FF	69.8%	62.8%
efficiency	-15%	-14%



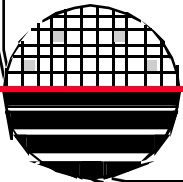
Rochester Institute of Technology
Microelectronic Engineering

BANDGAP OF VARIOUS SEMICONDUCTORS

$$E = h\nu = hc / \lambda$$

What wavelengths will not generate e-h pairs in silicon. Thus silicon is transparent or light of this wavelength or longer is not adsorbed?

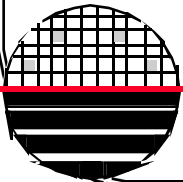
Semiconductor	Bandgap (eV) 300 K	Bandgap (eV) 0 K	λ_{\max} (μm) 300 K
BN	7.500	-	0.165
C	5.470	5.480	0.227
ZnS	3.680	3.840	0.337
GaN	3.360	3.500	0.369
ZnO	3.350	3.420	0.370
Alpha-SiC	2.996	3.030	0.414
CdS	2.420	2.560	0.512
GaP	2.260	2.340	0.549
BP	2.000	-	0.620
CdSe	1.700	1.850	0.729
AlSb	1.580	1.680	0.785
CdTe	1.560	-	0.795
GaAs	1.420	1.520	0.873
InP	1.350	1.420	0.919
Si	1.120	1.170	1.107
GaSb	0.720	0.810	1.722
Ge	0.660	0.740	1.879
PbS	0.410	0.286	3.024
InAs	0.360	0.420	3.444
PbTe	0.310	0.190	4.000
InSb	0.170	0.230	7.294
Sn	-	0.082	15.122 @ 0 K



TYPES OF PHOTODETECTORS

Device Type	Gain	Response Time (s)	Typical Temperature
Photomultiplier	$> 10^6$	10^{-7} to 10^{-9}	300 (sometimes cooled)
Photoconductor	1 to 10^6	10^{-3} to 10^{-8}	4.2 to 300
Metal-Semiconductor-Metal Photodetector	1 or less	10^{-10} to 10^{-12}	300
p-n Photodiode	1 or less	10^{-6} to 10^{-11}	300 (sometimes cooled to 77 K)
p-i-n Photodiode	1 or less	10^{-6} to 10^{-9}	300
Metal-Semiconductor Diode	1 or less	10^{-9} to 10^{-12}	300
Avalanche Diode	10^2 to 10^4	10^{-10}	300
Bipolar Phototransistor	10^2	10^{-6} to 10^{-8}	300
Bipolar Photo-Darlington	10^4	10^{-5} to 10^{-6}	300
Field-Effect Phototransistor	10	10^{-7}	300
CCD Cell (Metal-Insulator-Semiconductor Capacitor)	1 or less	10^{-5} to 10^{-8}	300 (sometimes cooled)

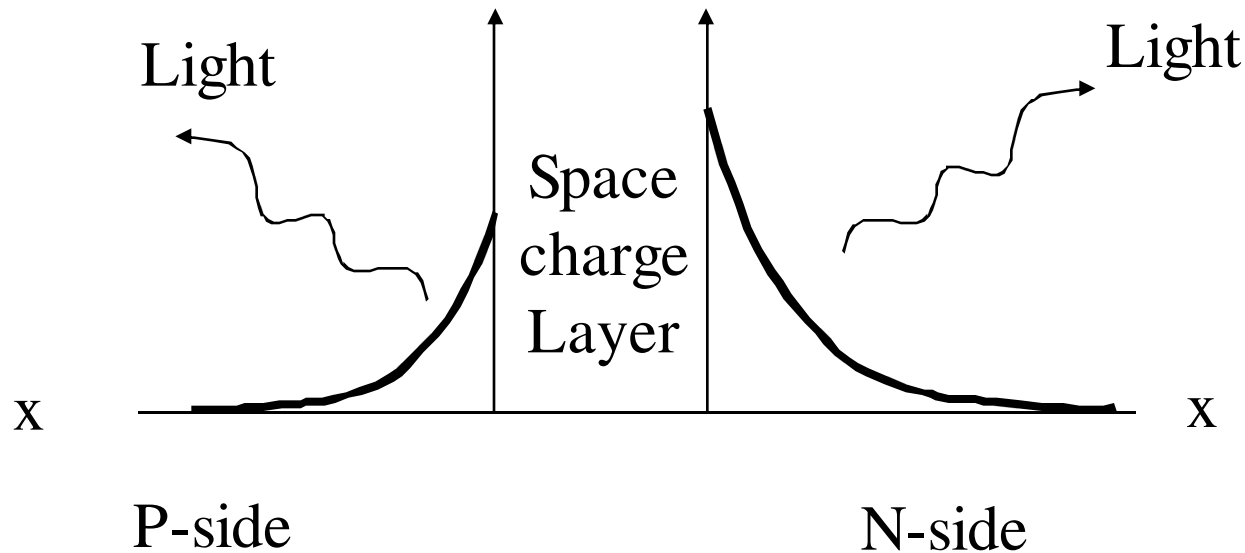
Gains and response times of some typical photodetectors (some are optimistic!). After Sze (1981). Note that the CCD cell, and some extrinsic photoconductors, are integrating detectors, and thus the response time figures can be somewhat misleading.



LIGHT EMITTING DIODES (LEDs)

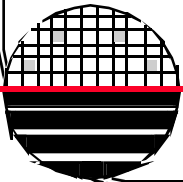
Electron concentration vs distance

Hole concentration vs distance



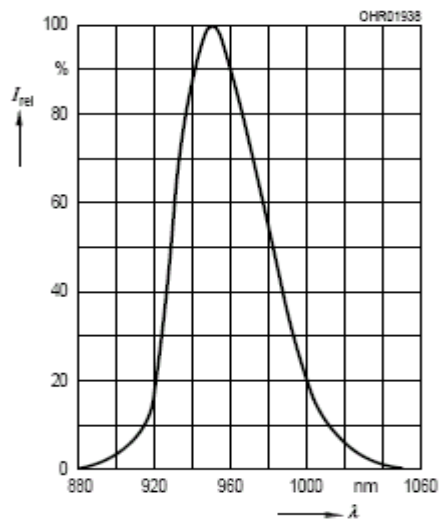
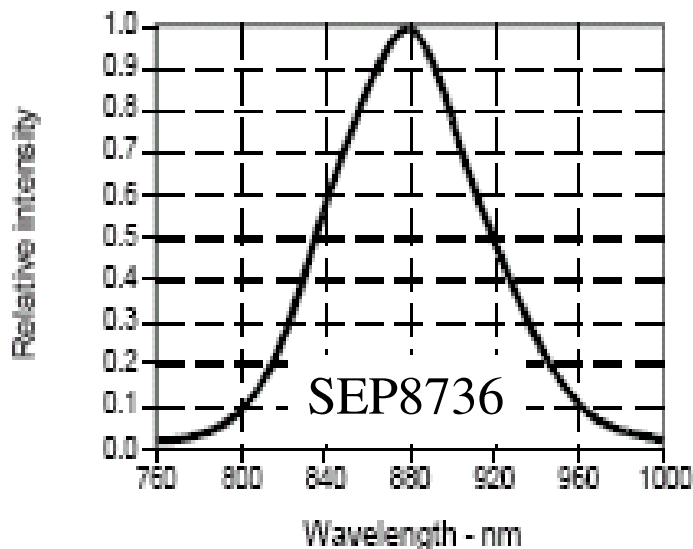
In the forward biased diode current flows and as holes recombine on the n-side or electrons recombine on the p-side, energy is given off as light, with wavelength appropriate for the energy gap for that material. $\lambda = h c / E$

h = Plank's constant
 c = speed of light



Diode Sensors Theory

LEDs



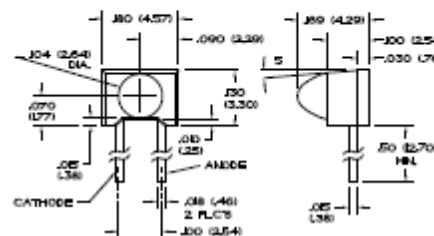
SFH4110



INFRADOT

OUTLINE DIMENSIONS in inches (mm)

Tolerance 3 plc decimals $\pm 0.005(0.12)$
2 plc decimals $\pm 0.020(0.51)$



SEP8736

AlGaAs Infrared Emitting Diode

ELECTRICAL CHARACTERISTICS (25°C unless otherwise noted)

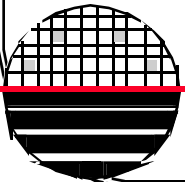
PARAMETER	SYMBOL	MIN	TYP	MAX	UNITS	TEST CONDITIONS
Irradiance ⁽¹⁾	H				mW/cm ²	$I_f=20$ mA
SEP8736-001		0.5				
SEP8736-002		1.2		3.0		
SEP8736-003		1.7				
Forward Voltage	V_F			1.7	V	$I_f=20$ mA
Reverse Breakdown Voltage	V_{BR}	3.0			V	$I_R=10$ μ A
Peak Output Wavelength	λ_p		880		nm	
Spectral Bandwidth	$\Delta\lambda$		80		nm	
Spectral Shift With Temperature	$\Delta\lambda_p/\Delta T$		0.2		nm/°C	
Beam Angle ⁽²⁾	θ		10		degr.	$I_f=Constant$
Radiation Rise And Fall Time	t_r, t_f		0.7		μ s	

Notes

1. Measured in mW/cm² into a 0.104 (2.64) diameter aperture placed 0.500 (12.7) from the lens tip.
2. Beam angle is defined as the total included angle between the half intensity points.

REFERENCES

1. Micromachined Transducers, Gregory T.A. Kovacs, McGraw-Hill, 1998.
2. Microsystem Design, Stephen D. Senturia, Kluwer Academic Press, 2001.
3. IEEE Journal of Microelectromechanical Systems.
4. Solar Cells, Martin A. Green, Prentice-Hall



HOMEWORK – DIODE SENSORS THEORY

1. Calculate the temperature change if a diodes forward voltage increases from 0.65 volts to 0.69 volts. Repeat for a change from 0.65 volts to 0.55 volts.
2. Calculate the change in capacitance expected for a diode heated from room temperature 300°K to 400°K.

